

Title: Transitioning EUV Lithography from Lab to Fab: status, challenges, and opportunities

Abstract: The long-anticipated shift to EUV lithography in high volume semiconductor manufacturing is finally occurring and leading to profound implications across the patterning space. There is a whole new set of needs in light sources, optics, masks, resists, metrology and other areas, and the technical challenges are substantial. In this presentation I will summarize the current status of EUV Lithography and explore challenges and potential solutions to future extension of the technology.